

Application No.	Applicant(s)
10/025,144	MOON ET AL.
Examin r	Art Unit
Stephen W. Smoot	2813

SEARCHED				
Class	Subclass	Date	Examiner	
438	626	4/27/2004	sws	
438	633	4/27/2004	sws	
438	687	4/27/2004	sws	
438	690	4/27/2004	sws	
438	691	4/27/2004	sws	
438	692	4/27/2004	sws	
451	41	4/27/2004	sws	

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INTERFERENCE SEARCHED				
Class	Subclass	Date	Examiner	
Same a	s Above	4/27/2004	J.W.J. sws	

SEARCH NOT (INCLUDING SEARCH		()
	DATE	EXMR
Key Words: CMP - Copper, Barrier Layer, Tantalum;	4/27/2004	SW. Sws
Linear Velocity; Carrier Head; Membrane; Retaining Ring; Polishing Pad; Platen;	4/27/2004	1.V.S sws
Pressure (psi); Rotation (rpm); Accelerate (rpm per second).	4/27/2004	\$10,8, sws
Search tools - EAST (attached): USPAT; US PG PUBS; Derwent;	4/27/2004	S.W.S sws
EPO; JPO; IBM TDB		